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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Fumio OHTAKE, et al.

Group Art Unit: **2814** ✓

Serial No.: **09/749,590**

Examiner: **MAI, Anh D.**

Filed: **December 28, 2000**

Confirmation No.: **4831**

For: **SEMICONDUCTOR DEVICE HAVING GATE ELECTRODES WITH
POLYMETAL STRUCTURE OF POLYCRYSTALLINE SILICON FILMS AND
METAL FILMS (as amended)**

Attorney Docket No.: **001752**

Customer Number: **38834**

AMENDMENT UNDER 37 CFR § 1.111

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

May 19, 2004

Sir:

In response to the Office Action dated February 19, 2004, please amend the above identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 10 of this paper.